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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Toshihiro YAMASHITA, et al.

Serial No.: 09/901,038

Group Art Unit: 1765

Filed: July 10, 2001 Examiner: D.V.D. Nguyen

PLASMA PROCESSING SYSTEM IN WHICH WAFER IS RETAINED BY For:

ELECTROSTACTIC CHUCK, PLASMA PROCESSING METHOD AND METHOD OF

MANUFACTURING SEMICONDUCTOR DEVICE

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop Non-Fee Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Noting the Office Action of June 26, 2003 wherein restriction has been required, Applicants hereby elects Species I (Figure 1) for prosecution in the above-identified application. Claims 1-7 are readable on the elected Species I.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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Date: July 18, 2003

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